5

10

15

25

30

## **CLAIMS**

What is claimed is:

- 1. A process comprising:
  - a. forming a donor element comprising:
    - i. a substrate; and
    - ii. a transfer layer, wherein the transfer layer comprises a fragile or thermally sensitive material and a protective layer located between the substrate and the fragile or thermally-sensitive layer;
  - b. placing the transfer layer of the donor element in contact with a receiver element; and
  - c. exposing selected areas of the donor element to laser radiation to transfer portions of the transfer layer onto a receiver element to form a positively imaged, patterned multilayer structure.
- 2. The process of Claim 1, wherein the donor element further comprises an ejection layer between the transfer layer and the substrate.
- 3. The process of Claim 2, wherein the ejection layer comprises an organic material with a decomposition temperature less than 275 °C.
- 4. The process of Claim 3, wherein the ejection layer is selected from the group consisting of nitrocellulose, polyvinylchloride, chlorinated polyvinylchloride, polymethylmethacrylate and polymethylmethacrylate copolymers
  - 5. The process of Claim 2, wherein the ejection layer further comprises a radiation-absorbing dye.
    - 6. The process of Claim 5, wherein the radiation absorbing dye is an infrared-absorbing dye.
    - 7. The process of Claim 6, wherein the infrared-absorbing dye is selected from the group consisting of 2-[2-[2-chloro-3-[(1,3-dihydro-1,3,3-trimethyl-2H-indol-2-ylidene)ethylidene]-1-cyclopenten-1-y1]ethyenyl]-1,3,3-trimethyl-3H-indolium, salt with trifluoromethane sulfonic acid (1:1); 2-[2-[2-chloro-3-[[1,3-dihydro-1,1-dimethyl-3-(4-sulfobutyl)-2H-benz[e]indol-2-ylidene]ethylidene]-1-cyclohexen-1-yl]ethenyl]-1,1-dimethyl-3-(4-sulfobutyl)-1H-benz[e]indolium, inner salt, free acid; and 4-[[3-[[2,6-bis(1,1-dimethylethyl)-4H-thiopyran-4-ylidene]methyl]-2-hydroxy-4-oxo-2-cyclobuten-1-ylidene]methyl]-2,6-bis(1,1-dimethylethyl)-thiopyrylium, inner salt.

- 8. The process of Claim 1, wherein the substrate of the donor element is a flexible film.
- 9. The process of Claim 8, wherein the flexible film comprises a polymer selected from the group consisting of polyesters, polyether sulfone, polyvinyl chloride, polyimides, poly(vinyl alcohol-co-acetal), polyethylene, and cellulose esters.
- 10. The process of Claim 1, wherein the fragile or thermally sensitive material comprises an organic electroactive material.

5

10

25

30

35

- 11. The process of Claim 10, wherein the organic electroactive material comprises a light-emitting polymeric material or a light-emitting small molecule, the protective layer comprises a charge injection layer, and the receiver element comprises a substrate and an anode layer.
- 12. The process of Claim 11, wherein the anode layer comprises indium tin oxide.
- 13. A polymer light-emitting diode manufactured according to the process of Claim 12.
  - 14. The process of Claim 1, wherein the fragile or thermally sensitive material comprises an organic or inorganic semiconductor and the protective layer comprises a dielectric material.
- 15. The process of Claim 14, wherein the organic semiconductor is selected from the group consisting of pentacene, sexithiophene, tetracene, polythieneylenevinylene, thiophene oligomers, benzothiophene dimers and polyacetylenes.
  - 16. The process of Claim 14, wherein the dielectric material is selected from the group consisting of polyhydroxystyrene, polyvinylphenol, polyvinylpyridine, glass resin, fluorinated copolymers and methacrylic copolymers.
  - 17. The process of Claim 14, wherein the receiver element comprises a substrate and a patterned conductive layer.
  - 18. The process of Claim 17, wherein the substrate of the receiver element comprises mineral-filled polyester, ivory paper or spunbonded polyolefin.
  - 19. The process of Claim 14, wherein the receiver element further comprises an adhesive layer.
  - 20. The process of Claim 19, wherein the adhesive layer comprises a polymer selected from the group consisting of polycarbonates; polyurethanes; polyesters; polyvinylchloride; styrene/acrylonitrile

copolymers; poly(caprolactone); vinylacetate copolymers with at least one of ethylene and vinyl chloride; (meth)acrylate homopolymers; (meth)acrylate copolymers; and mixtures thereof.

- 21. The process of Claim 14, wherein the donor element further comprises an ejection layer between the transfer layer and the substrate.
- 22. The process of Claim 14, wherein the donor element further comprises a heating layer between the substrate and the transfer layer.
- 23. The process of Claim 22, wherein the heating layer comprises a thin layer of Ni, Al or Cr.
- 10 24. The process of Claim 17, wherein the patterned conductive layer comprises source and drain for a transistor.
  - 25. The process of Claim 24, wherein the patterned conductive layer further comprises interconnects.
    - 26. A thermally imageable donor element, comprising:
- a. a substrate;

5

- b. a heating layer;
- c. a protective layer; and
- d. a fragile or thermally sensitive layer.
- 27. The thermally imageable donor element of Claim 26, wherein;
  the substrate is a flexible film comprising a polymer selected
  from the group consisting of polyesters, polyether sulfone,
  polyvinyl chloride, polyimides, poly(vinyl alcohol-co-acetal),
  polyethylene, and cellulose esters;
  the heating layer comprises a thin layer of Ni, Al, or Cr;
  the protective layer comprises a dielectric material or a charge
  injection material; and
  the fragile or thermally sensitive layer comprises an organic
  semiconductor, or a light-emitting polymer, or a light-emitting
  small molecule.
- 28. The donor element of Claim 27, wherein the fragile or thermallysensitive layer is deposited on the protective layer via evaporation or casting from solution.